



<b>[WA2] Plasmas for Environmental Technology</b>	
<b>Date / Time</b>	July 25 (Wed.), 2018 / 13:40-15:10
<b>Place</b>	Room A (#104~106)
<b>Session Chair(s)</b>	Heeyeop Chae (Sungkyunkwan Univ., Korea)

**WA2-1 [Invited] 13:40-14:10**

**Nonthermal Plasma Enabled Electrification of Energy and Materials Conversion Processes**

Tomohiro Nozaki, Seigo Kameshima, and Zunrong Sheng

*Tokyo Inst. of Tech., Japan*

**WA2-2 14:10-14:30**

**Plasma Etching of SiO<sub>2</sub> Perfluorinated and Partially Fluorinated Fluoro Ethers**

Jun-Hyun Kim, Jin-Su Park, and Chang-Koo Kim

*Ajou Univ., Korea*

**WA2-3 14:30-14:50**

**Realistic Surface Reaction Modeling of Fluorocarbon Plasma Etch Process**

Hae Sung You, Yeong Geun Yook, Jae Hyeong Park, and Yeon Ho Im

*Chonbuk Nat'l Univ., Korea*

**WA2-4 14:50-15:10**

**Ethylene Treatment Using Nanosecond Pulsed Streamer Discharge**

Asuki Iwasaki, Yasuaki Torigoe, Douyan Wang, and Takao Namihira

*Kumamoto Univ., Japan*